

B) depositing a thin film material selected from the group consisting of: an organic molecule, a short-chain organic oligomer, a long-chain organic polymer, a photoresist, an organic-inorganic hybrid material, a metallo-organic complex, a nanoparticle of metal, a nanoparticle of metal oxide, a nanoparticle of semiconductor, a silica particle, an inorganic salt, and a mixture thereof, on a surface of a substrate having thereon a patterned underlayer of a self-assembled monolayer.

B2) 24. (Amended) The method of claim 22, wherein said organic-inorganic hybrid material is selected from the group consisting of: $(C_6H_5C_2H_4NH_3)_2SnI_4$, $(C_4H_9NH_3)_2CH_3NH_3Sn_2I_7$, $(C_6H_5C_2H_4NH_3)_2CH_3NH_3Sn_2I_7$, $(H_3NC_4H_8NH_3)_2SnI_4$ and a mixture thereof.

Sub C) 25. (Amended) The method of claim 22, wherein said photoresist is a positive working, deep UV photoresist.

26. (Amended) The method of claim 22, wherein said long-chain organic polymer is polymethyl methacrylate/ methyl methacrylate copolymer.

27. (Amended) The method of claim 22, wherein said metallo-organic complex is tin 2-ethylhexanoate.

Please add the following new claim:

B) -- 31. The method of claim 30, wherein said thin film material is selected from the group consisting of: an organic molecule, a short-chain organic oligomer, a long-chain organic polymer, a photoresist, an organic-inorganic hybrid material, a metallo-organic complex, a nanoparticle of metal, a nanoparticle of metal oxide, a nanoparticle of semiconductor, a silica particle, an inorganic salt, and a mixture thereof, on a surface of a substrate having thereon a patterned underlayer of a self-assembled monolayer. --